

Polysilicon Depletion & Quantum Effects

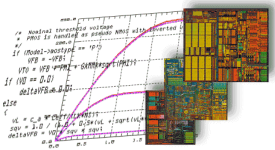
Polysilicon Gate Depletion:

- Potential & Charge Balance in the MOSFET Including Poly Depletion
- Pinch-Off Surface Potential & Inversion Charge
- Linearisation of the Inversion Charge vs. Surface Potential
- Poly Depletion in Accumulation (MOSCAP's)

Quantum Mechanical Effects:

- Total Charge in the Semiconductor Including Quantum Effects, "Bandgap Widening"
- Extension of the General Charge-Voltage Expression
- Evaluation of the Quantum Correction
- The "Electric" Oxide Capacitance
- Extension of the EKV Current-Voltage Expression

Summary



EKV3.0: Polysilicon Gate Depletion

Charge & Potential Balance in the MOSFET with Polydepletion

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Charge Balance in the MOS Structure

$$Q_g = -(Q_{ox} + Q_i + Q_b)$$

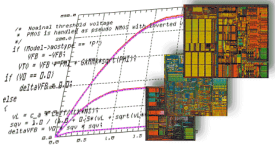
- for an NMOS in inversion (N-type polysilicon gate), $Q_g > 0$ is entirely produced by the fixed charges in the depleted layer at the lower face of the gate
- potential drop $\Delta\Psi_g$ across the depleted gate layer can be evaluated using the depletion approximation:

$$Q_g = C_{ox} \cdot \Gamma_g \cdot \sqrt{\Delta\Psi_g}$$

$$\Gamma_g = \frac{\sqrt{2 \cdot q \cdot \epsilon_{si} \cdot N_g}}{C_{ox}} : \text{gate modulation factor}$$

that is:

$$\Delta\Psi_g = \left(\frac{Q_g}{\Gamma_g \cdot C_{ox}} \right)^2$$



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Charge & Potential Balance in the MOSFET with Polydepletion

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Potential Balance in the MOS Structure

$$V_G = \Phi_{ms} + \Psi_s + \Delta\Psi_{ox} + \Delta\Psi_g \quad (\text{voltages referred to bulk})$$

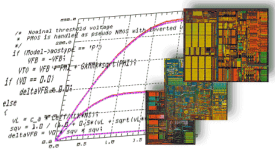
- replacing :

$$V_G = \Phi_{ms} + \Psi_s + \frac{Q_g}{C_{ox}} + \left(\frac{Q_g}{\Gamma_g \cdot C_{ox}} \right)^2 = \Phi_{ms} + \Psi_s - \frac{Q_{ox} + Q_i + Q_b}{C_{ox}} + \left(\frac{Q_{ox} + Q_i + Q_b}{\Gamma_g \cdot C_{ox}} \right)^2$$

- rearranging :

$$V_G - \left[\Phi_{ms} - \frac{Q_{ox}}{C_{ox}} + \left(\frac{Q_{ox}}{\Gamma_g \cdot C_{ox}} \right)^2 \right] = \Psi_s - \frac{Q_i + Q_b}{C_{ox}} \cdot \left(1 - \frac{2 \cdot Q_{ox}}{\Gamma_g^2 \cdot C_{ox}} \right) + \left(\frac{Q_i + Q_b}{\Gamma_g \cdot C_{ox}} \right)^2$$

$\underbrace{\hspace{10em}}_{V_{FB'}}$



Pinch-Off Surface Potential

- $Q_i(\Psi_P) = 0$ by definition of Ψ_P . Then :

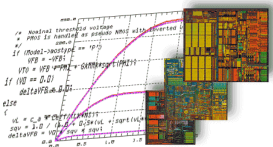
$$V_G - V_{FB'} = \Psi_P - \frac{Q_b(\Psi_P)}{C_{ox}} \cdot \left(1 - \frac{2 \cdot Q_{ox}}{\Gamma_g^2 \cdot C_{ox}} \right) + \left(\frac{Q_b(\Psi_P)}{\Gamma_g \cdot C_{ox}} \right)^2$$

- uniformly doped substrate $\Rightarrow Q_b(\Psi_P) = -\Gamma_b \cdot C_{ox} \cdot \sqrt{\Psi_P}$:

$$V_G - V_{FB'} = \Psi_P \cdot \left[1 + \left(\frac{\Gamma_b}{\Gamma_g} \right)^2 \right] + \Gamma_b \cdot \sqrt{\Psi_P} \cdot \left(1 - \frac{2 \cdot Q_{ox}}{\Gamma_g^2 \cdot C_{ox}} \right) + \left(\frac{Q_b(\Psi_P)}{\Gamma_g \cdot C_{ox}} \right)^2$$

then :

$$\Psi_P = \left[\sqrt{\frac{V_G - V_{FB'}}{1 + \left(\frac{\Gamma_b}{\Gamma_g} \right)^2} + \left(\frac{\Gamma_{eq}}{2} \right)^2} - \frac{\Gamma_{eq}}{2} \right]^2 \quad \text{with} \quad \Gamma_{eq} = \Gamma_b \cdot \left(\frac{\Gamma_g^2 - 2 \cdot \frac{Q_{ox}}{C_{ox}}}{\Gamma_g^2 + \Gamma_b^2} \right)$$



Inversion Charge vs. Surface Potential

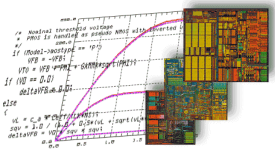
- Once Ψ_P is known $Q_i(\Psi_S, \Psi_P)$ is :

$$-\frac{Q_i}{C_{ox}} = \frac{(1 + \delta_{pd}) \cdot (\Psi_P - \Psi_S) + \Gamma_b \cdot (\sqrt{\Psi_P} - \sqrt{\Psi_S})}{\left(\frac{1}{2} - \delta_{ox} + \delta_{pd} \cdot \frac{\sqrt{\Psi_S}}{\Gamma_b} \right) + \sqrt{\left(\frac{1}{2} - \delta_{ox} + \delta_{pd} \cdot \frac{\sqrt{\Psi_S}}{\Gamma_b} \right)^2 + \delta_{pd} \cdot \left[(1 + \delta_{pd}) \cdot \frac{\Psi_P - \Psi_S}{\Gamma_b^2} + \frac{\sqrt{\Psi_P} - \sqrt{\Psi_S}}{\Gamma_b} \right]}}$$

with $\delta_{ox} = \frac{Q_{ox}}{\Gamma_g^2 \cdot C_{ox}}$ and $\delta_{pd} = \left(\frac{\Gamma_b}{\Gamma_g} \right)^2$

- Note that without PD ($\Gamma_g \gg 1$), one simply has :

$$-\frac{Q_i}{C_{ox}} = (\Psi_P - \Psi_S) + \Gamma_b \cdot (\sqrt{\Psi_P} - \sqrt{\Psi_S})$$



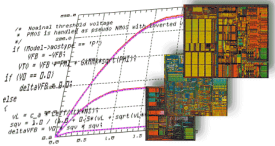
Charge Slope Factor n_q

- Rewriting $-\frac{Q_i}{C_{ox}}$ as :

$$-\frac{Q_i}{C_{ox}} = n_q \cdot (\Psi_P - \Psi_S)$$

yields, by identification :

$$n_q(\Psi_P, \Psi_S) = \frac{1 + \delta_{pd} + \frac{\Gamma_b}{\sqrt{\Psi_P} + \sqrt{\Psi_S}}}{\left(\frac{1}{2} - \delta_{ox} + \delta_{pd} \cdot \frac{\sqrt{\Psi_S}}{\Gamma_b}\right) + \sqrt{\left(\frac{1}{2} - \delta_{ox} + \delta_{pd} \cdot \frac{\sqrt{\Psi_S}}{\Gamma_b}\right)^2 + \left(1 + \delta_{pd} + \frac{\Gamma_b}{\sqrt{\Psi_P} + \sqrt{\Psi_S}}\right) \cdot \frac{\Psi_P - \Psi_S}{\Gamma_g^2}}}$$

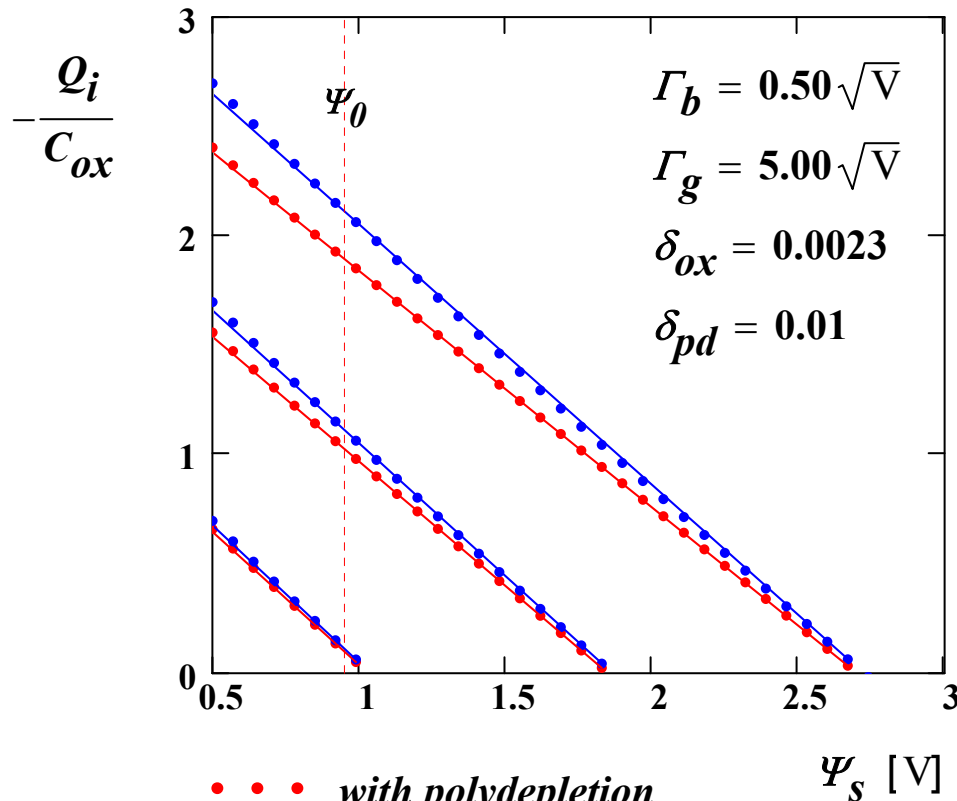


EKV3.0: Polysilicon Gate Depletion

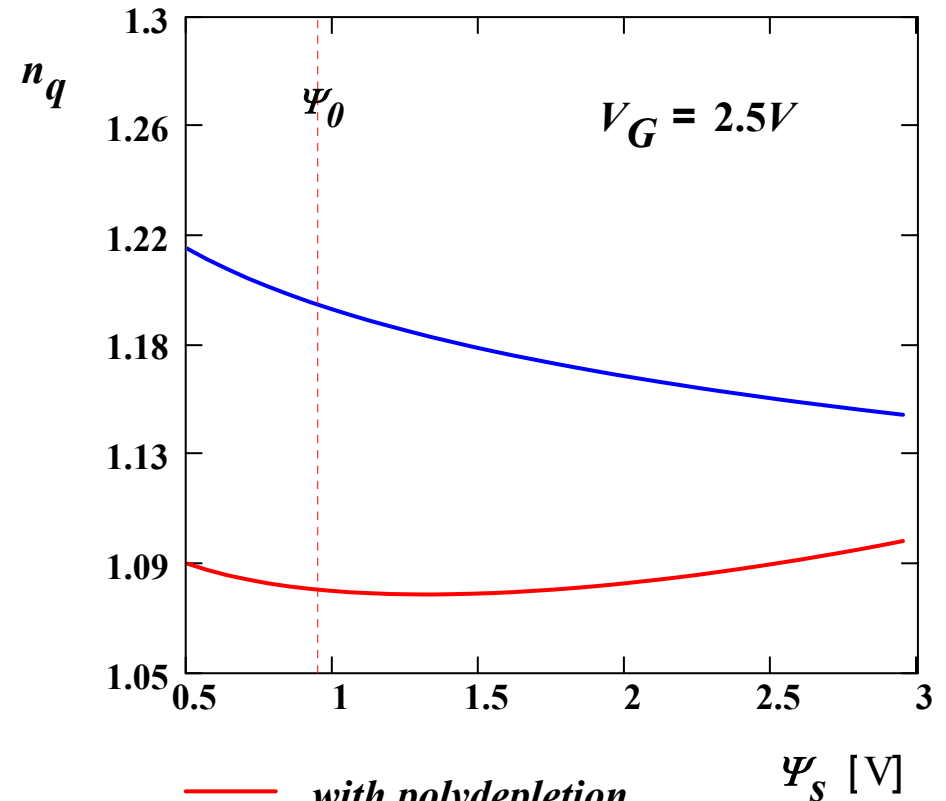
Linearisation of the Inversion Charge vs. Surface Potential

$V_G \equiv 0.5V, 1.5V .. 2.5V$

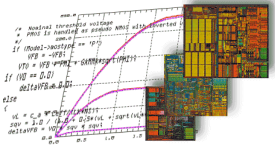
$$n_q = -\frac{Q_i}{C_{ox}(\Psi_P - \Psi_S)}$$



- • • *with polydepletion*
- • • *no polydepletion*
- *linear approximation (with polydepletion)*
- *linear approximation (no polydepletion)*



- *with polydepletion*
- *no polydepletion*

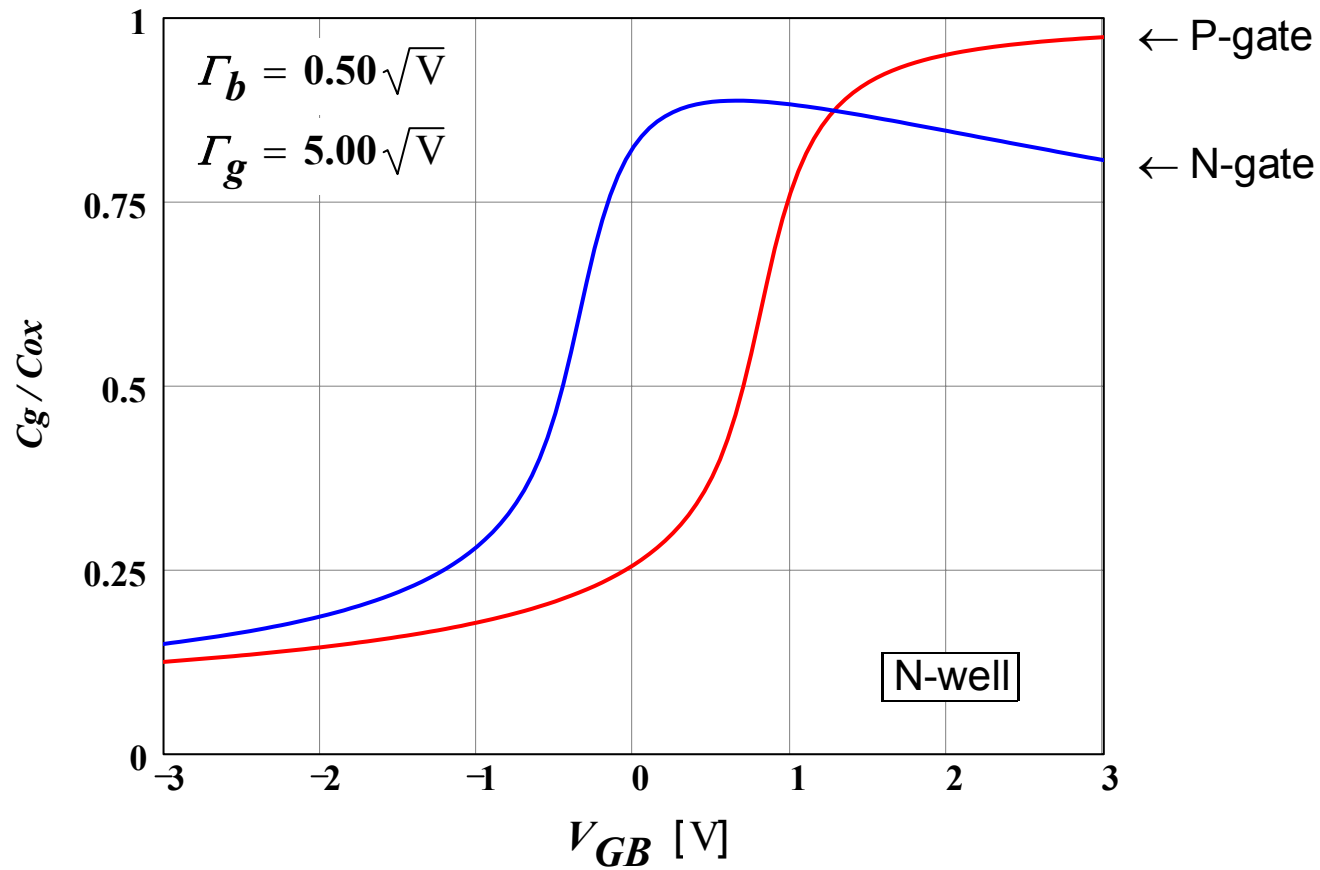


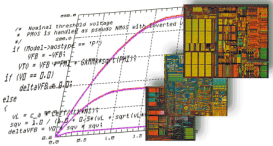
EKV3.0: Polysilicon Gate Depletion

MOSCAP's & Poly Depletion in Accumulation

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Case study: N-well MOSCAP, N-gate vs. P-gate





Total Charge in the Semiconductor Including Quantum Effects

- quantum confinement due to sharp band bending near the oxide (high vertical field, high bulk doping) :

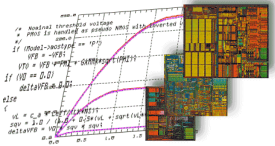
$$Q_{Si} = -\text{sign}(\Psi_s) \cdot \Gamma_b \cdot C_{ox} \cdot \sqrt{U_T \cdot \left(e^{-\frac{\Psi_s + \Delta\Psi_v}{U_T}} - 1 \right) + U_T \cdot e^{-\frac{2 \cdot \Phi_F + V}{U_T}} \cdot \left(e^{-\frac{\Psi_s - \Delta\Psi_c}{U_T}} - 1 \right) + \Psi_s}$$

|----- holes -----| |----- electrons -----| |--- fixed charges

where $\Delta\Psi_c$ and $\Delta\Psi_v$ correspond to the difference between the first allowed energy level and the bottom of the conduction band (depletion & inversion), and top of the valence band (accumulation), respectively

- $\Delta\Psi_c$ and $\Delta\Psi_v$ are both positive and can be related to the electric field (i.e. the charges) in the silicon :

$$\Delta\Psi_c = \begin{cases} \Delta\Psi_c(-Q_b, -Q_i) > 0 & \text{if } \Psi_s > 0 \\ 0 & \text{if } \Psi_s \leq 0 \end{cases} \quad \Delta\Psi_v = \begin{cases} 0 & \text{if } \Psi_s \geq 0 \\ \Delta\Psi_v(Q_b) > 0 & \text{if } \Psi_s < 0 \end{cases}$$



Analysis in Depletion & Inversion

- charge sheet approximation
- linearisation of the inversion charge wrt. surface potential :

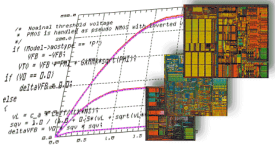
$$-Q_i = n_q \cdot C_{ox} \cdot (\Psi_P - \Psi_S) \quad \Rightarrow \quad \Psi_S = \Psi_P - \frac{-Q_i}{n_q \cdot C_{ox}}$$

- quantum correction linearised in terms of $-Q_i$ around $Q_i = 0$:

$$\Delta\Psi_c(-Q_b, -Q_i) = \Delta\Psi_c(\Psi_P, Q_i = 0) + \frac{d\Delta\Psi_c(\Psi_P, -Q_i)}{d(-Q_i)} \cdot (-Q_i) = \Delta\Psi_{c,p} + \delta_{qm} \cdot \frac{-Q_i}{n_q \cdot C_{ox}}$$

- from $Q_{Si} = Q_b + Q_i = F(V_G, \Psi_S, V)$, the charge-voltage relationship is derived:

$$2 \cdot \frac{-Q_i \cdot (1 + \delta_{qm})}{2 \cdot n_q \cdot C_{ox} \cdot U_T} + \ln \left[\frac{-Q_i \cdot (1 + \delta_{qm})}{2 \cdot n_q \cdot C_{ox} \cdot U_T} \right] = \frac{\Psi_P - 2 \cdot \Phi_F - V}{U_T} - \frac{\Delta\Psi_{c,p}}{U_T} - \ln \left(\frac{4 \cdot n_q}{1 + \delta_{qm}} \cdot \frac{\sqrt{\Psi_P}}{\Gamma_b} \right)$$



Extending the EKV Formalism to Include QM

- extension of the pinch-off voltage definition :

$$V'_P = \Psi_P - (\Psi_0 + \Delta\Psi_0)$$

that is, due to quantum effects, Ψ_0 is increased by:

$$\Delta\Psi_0 = \Delta\Psi_{c,p} - U_T \cdot \ln(1 + \delta_{qm}) \approx \Delta\Psi_{c,p} - \delta_{qm} \cdot U_T$$

- the "electric" oxide capacitance :

$$C'_{ox} = C'_{ox}(\Psi_P) = \frac{C_{ox}}{1 + \delta_{qm}(\Psi_P)} < C_{ox}$$

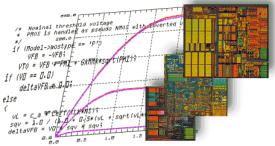
- normalisation:

$$2 \cdot \frac{-Q_i}{2 \cdot n_q \cdot C'_{ox} \cdot U_T} + \ln \left(\frac{-Q_i}{2 \cdot n_q \cdot C'_{ox} \cdot U_T} \right) = \frac{V'_P - V}{U_T}$$

|_____ q' _____|
|_____ q' _____|

or

$$2 \cdot q' + \ln(q') = v'_p - v$$



Bandgap Widening

- $\Delta\Psi_c$ is primarily a function of the effective vertical electric field :

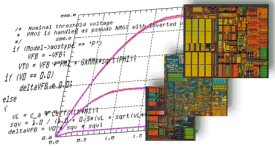
$$\Delta\Psi_c = A_{qm} \cdot \left(|Q_b + \eta \cdot Q_i| \right)^{\frac{2}{3}} = A_{qm} \cdot \left[-Q_b \left(\Psi_P - \frac{-Q_i}{n_q \cdot C_{ox}} \right) + \eta \cdot (-Q_i) \right]^{\frac{2}{3}} = \Delta\Psi_c(\Psi_P, -Q_i)$$

- simplified linear approximation around $Q_i = 0$:

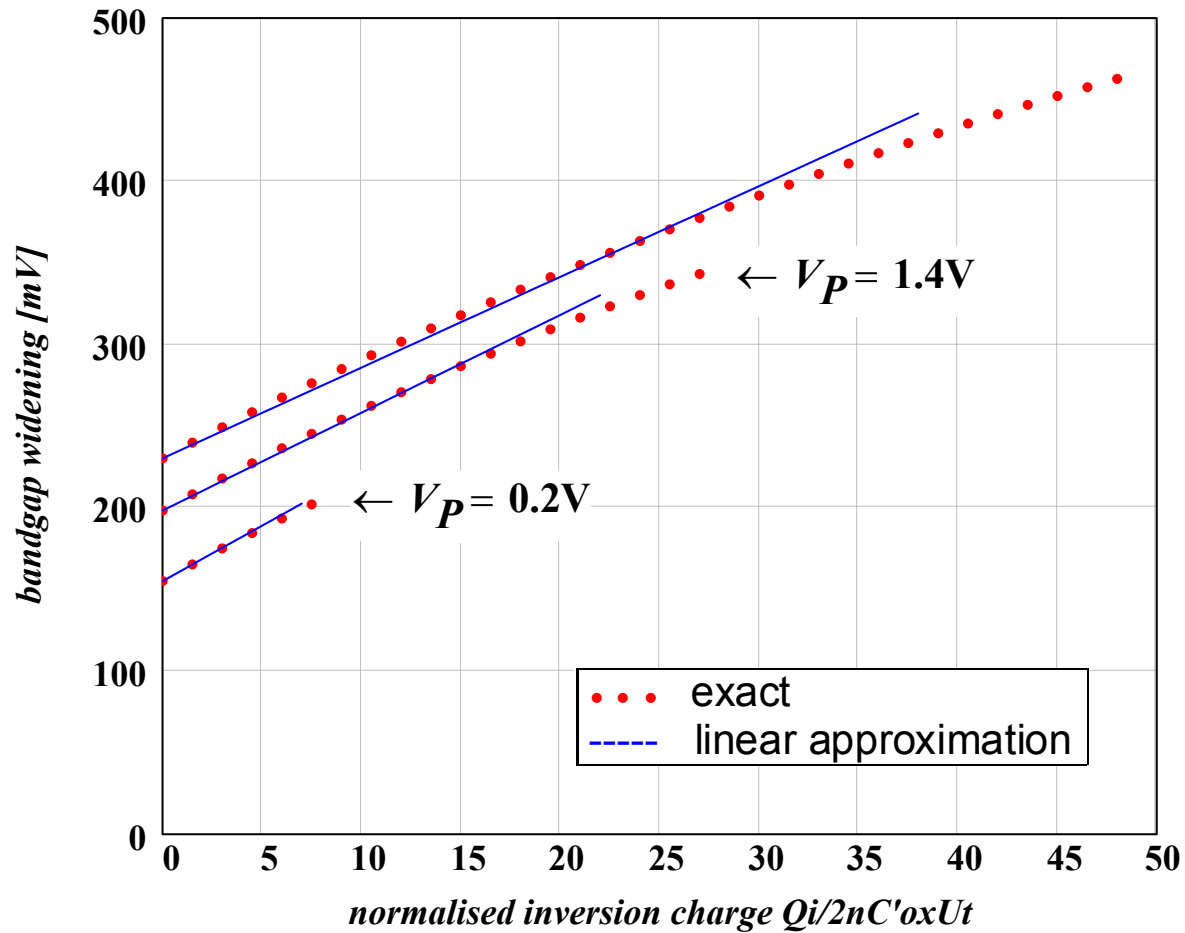
$$\Delta\Psi_c = A_{qm} \cdot \left(\Gamma_b \cdot C_{ox} \cdot \sqrt{\Psi_P} \right)^{\frac{2}{3}} + \delta_{qm} \cdot \frac{-Q_i}{n_q \cdot C_{ox}}$$

with

$$\delta_{qm} = \frac{2}{3} \cdot A_{qm} \cdot C_{ox} \cdot \left(\eta \cdot n_{q0} - \frac{\Gamma_b}{2 \sqrt{2 \cdot \Phi_F}} \right) \cdot \left(\Gamma_b \cdot C_{ox} \cdot \sqrt{\Psi_P} \right)^{-\frac{1}{3}}$$



Bandgap Widening (cont'd)



← $V_P = 2.7V$

← $V_P = 1.4V$

← $V_P = 0.2V$

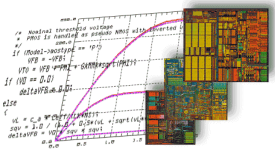
$$2 \cdot \Phi_F = 0.90 \text{ V}$$

$$t_{ox} = 2 \text{ nm}$$

$$\Gamma_b = 0.5\sqrt{V}$$

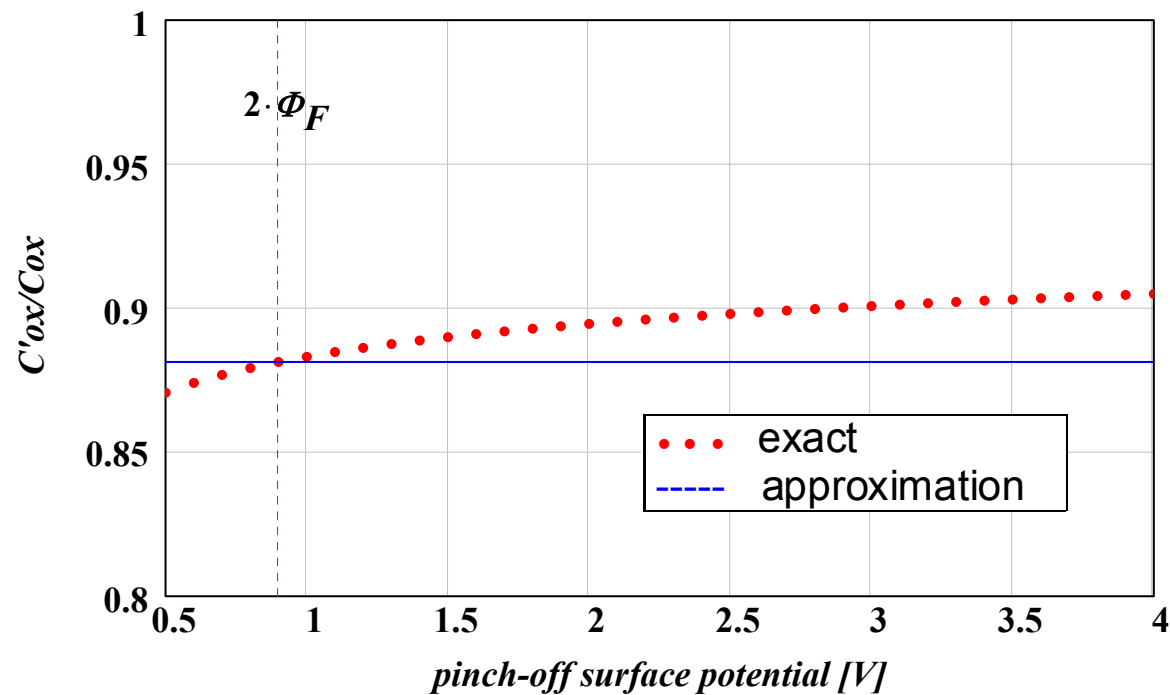
$$\delta_{pd} = 0.0$$

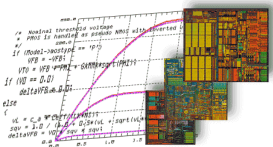
$$\eta = 0.75$$



The Apparent Oxide Capacitance

$$C'_{ox} = \frac{C_{ox}}{1 + \delta_{qm}} = \frac{C_{ox}}{1 + \frac{2}{3} \cdot A_{qm} \cdot C_{ox} \cdot \left(\eta \cdot n_{q0} - \frac{\Gamma_b}{2 \sqrt{2 \cdot \Phi_F}} \right) \cdot \left(\Gamma_b \cdot C_{ox} \cdot \sqrt{\Psi_P} \right)^{-\frac{1}{3}}}$$





- Drift-diffusion transport equation :

$$I_D = I_{drift} + I_{diff} = \mu \cdot W \cdot \left(Q_i \cdot E(x) + U_T \cdot \frac{dQ_i}{dx} \right)$$

- Electric field experienced by the mobile carriers :

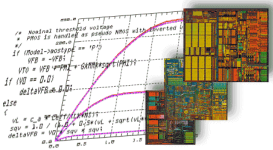
$$E(x) = -\frac{d}{dx}(\Psi_s - \Delta\Psi_c) = -\frac{d\Psi_s}{dx} - \left(\frac{\delta_{qm}}{n_q \cdot C_{ox}} \right) \cdot \frac{dQ_i}{dx}$$

- Linearised relation between the inversion charge and the surface potential:

$$-Q_i = n_q \cdot C_{ox} \cdot (\Psi_P - \Psi_s) \quad \text{i.e.} \quad dQ_i = n_q \cdot C_{ox} \cdot d\Psi_s$$

then :

$$I_D = \mu \cdot W \cdot \left[\frac{-Q_i}{n_q \cdot C_{ox}} \cdot (1 + \delta_{qm}) + U_T \right] \cdot \frac{dQ_i}{dx} = \mu \cdot W \cdot \left(\frac{-Q_i}{n_q \cdot C'_{ox}} + U_T \right) \cdot \frac{dQ_i}{dx}$$

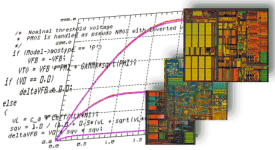


Polysilicon Depletion

- occurs in depletion and inversion (normal MOSFET: type of gate opposite to that of bulk) or in accumulation (MOSCAP's: gate same type as bulk)
- pinch-off voltage is reduced, equivalent to :

$$V_G - V_{FB} \Rightarrow \frac{V_G - V_{FB} - \left(\frac{Q_{ox}}{\Gamma_g \cdot C_{ox}} \right)^2}{1 + \left(\frac{\Gamma_b}{\Gamma_g} \right)^2} \quad \Gamma_b \Rightarrow \Gamma_b \cdot \left(\frac{\Gamma_g^2 - 2 \cdot \frac{Q_{ox}}{C_{ox}}}{\Gamma_g^2 + \Gamma_b^2} \right)$$

- slope factor n_q can be strongly modified, but the charge-voltage linearisation scheme remains valid
- PD reduces the MOS capacitances due to an increased apparent dielectric thickness
- Adds one model parameter: **Ngate** or equivalently **GammaG**

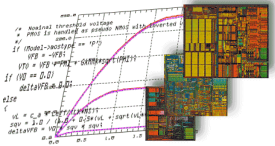


Quantum Effects

- bandgap widening is accounted for with $\Delta\Psi_0$ (reduced V_P for a given Ψ_p) and "electric" capacitance $C'_{ox} < C_{ox}$
- the EKV charge-voltage & current-voltage relations remain valid with the following normalisation :

$$q = \frac{-Q_i}{2 \cdot n_q \cdot C'_{ox} \cdot U_T} \quad \text{and} \quad i = \frac{I_d}{2 \cdot n_q \cdot \frac{W}{L} \cdot \mu_0 \cdot C'_{ox} \cdot U_T^2}$$

- QM impacts both accumulation and inversion
- Adds no model parameter, but a flag to turn off QM for convenience



EKV3.0: Polysilicon Depletion & Quantum Mechanical Effects

Summary

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$$t_{ox} = 2 \text{ nm} \quad \Gamma_b = 0.37\sqrt{V} \quad \Gamma_g = 5.0\sqrt{V}$$

